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In re Application of: Yasuyuki TAMURA et al.

Serial No.: 10/765,894

Group Art Unit: UNASSIGNED

Filed: January 29, 2004

Examiner: **UNASSIGNED**

For:

SEMICONDUCTOR DEVICE AND METHOD FOR FABRICATING THE SAME

INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 CFR 1.97(b)

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

April 29, 2004

Sir:

Applicants direct the attention of the Patent and Trademark Office to the documents listed on the attached Form PTO-1449. A copy of each listed document is attached.

No fee or certification is required in connection with this Information Disclosure Statement, because it is being submitted prior to the issuance of a first official action on the merits or expiration of the three month period following the filing date or the entry of the national stage of the above-captioned application.

The above information is presented so that the Patent and Trademark Office can, in the first instance, determine any materiality thereof to the claimed invention. Applicants respectfully request that the information be expressly considered during the prosecution of this application and that the documents cited in the attached Form PTO-1449 be made of record therein and appear on the first page of any patent to issue therefrom.



The Commissioner is authorized to charge our Deposit Account No. 50-2866 for any fee that is required to effect consideration of this statement.

Respectfully submitted,

WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP

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Enclosures: PTO-1449 and <u>3</u> references

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DISCLOSURE CITATION		Œ	Applicant(s): Yasuyuki TAMURA et al.						
PTO-1449			Filing Date: January 29, 2004			Group Art Unit: Unassigned			
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FOREIGN PATENT DOCUMENTS									
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Examiner				Da	te Conside	red			